

DOCKET NO.: DPSR-0002/SR0020USPCT
Application No.: 10/523,492
Office Action Dated: October 18, 2007

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Andrew E. Feiring et al.

Confirmation No.: **1866**

Application No.: **10/523,492**

Group Art Unit: **1796**

Filing Date: **February 3, 2005**

Examiner: **Henry S. Hu**

For: **Photoresists, Fluoropolymers And Processes For 157 NM Microlithography**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

REPLY PURSUANT TO 37 CFR § 1.111

In response to the Official Action dated **October 18, 2007**, reconsideration is respectfully requested in view of the amendments and/or remarks as indicated below:

- ☒ **Amendments to the Specification** begin on page 2 of this paper.
- ☒ **Amendments to the Claims** are reflected in the listing of the claims which begins on page 3 of this paper.
- ☐ **Amendments to the Drawings** begin on page of this paper and include an attached replacement sheet.
- ☒ **Remarks** begin on page 6 of this paper.